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Atty. Docket No. 8029-1041

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IN THE UNITED STATES PATENT AND TRADEMARK OF 2003

In re application of

TECHNOLOGY CENTER 2800

Masaru TSUKIJI

Confirmation No. 4695

Serial No. 09/761,693

GROUP 2826

Filed January 18, 2001

Examiner Fetsum Abraham

STRUCTURE AND MANUFACTURING METHOD OF NON-VOLATILE FLASH MEMORY

## **AMENDMENT**

Commissioner for Patents

Washington, D.C. 20231

Sir:

Responsive to the Official Action of October 21, 2002, please amend the above-identified application as follows:

## IN THE CLAIMS:

Amend claim 3 as follows:

--3. (amended) A structure of a non-volatile flash memory that is a NOR type non-volatile flash memory, provides floating gates and a common source line, wherein:

an impurity gradient distribution of a source in a memory cell adjacent to where said source joins a semiconductor substrate is gradual.—

## REMARKS

The indication that claims 1-2 and 4-12 have been allowed is acknowledged with thanks. Claim 3 was rejected under

(when